

**Abstract of the Disclosure**

In the present invention, a substrate with exposure light from an exposure light source is irradiated before a 5 projection exposure beforehand. A reflectance of this exposure light from the substrate is measured. An appropriate intensity of exposure light for the substrate is determined by referring to the reflectance. Then, a mask pattern is projected onto the substrate by irradiating with exposure light of the determined 10 intensity.

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